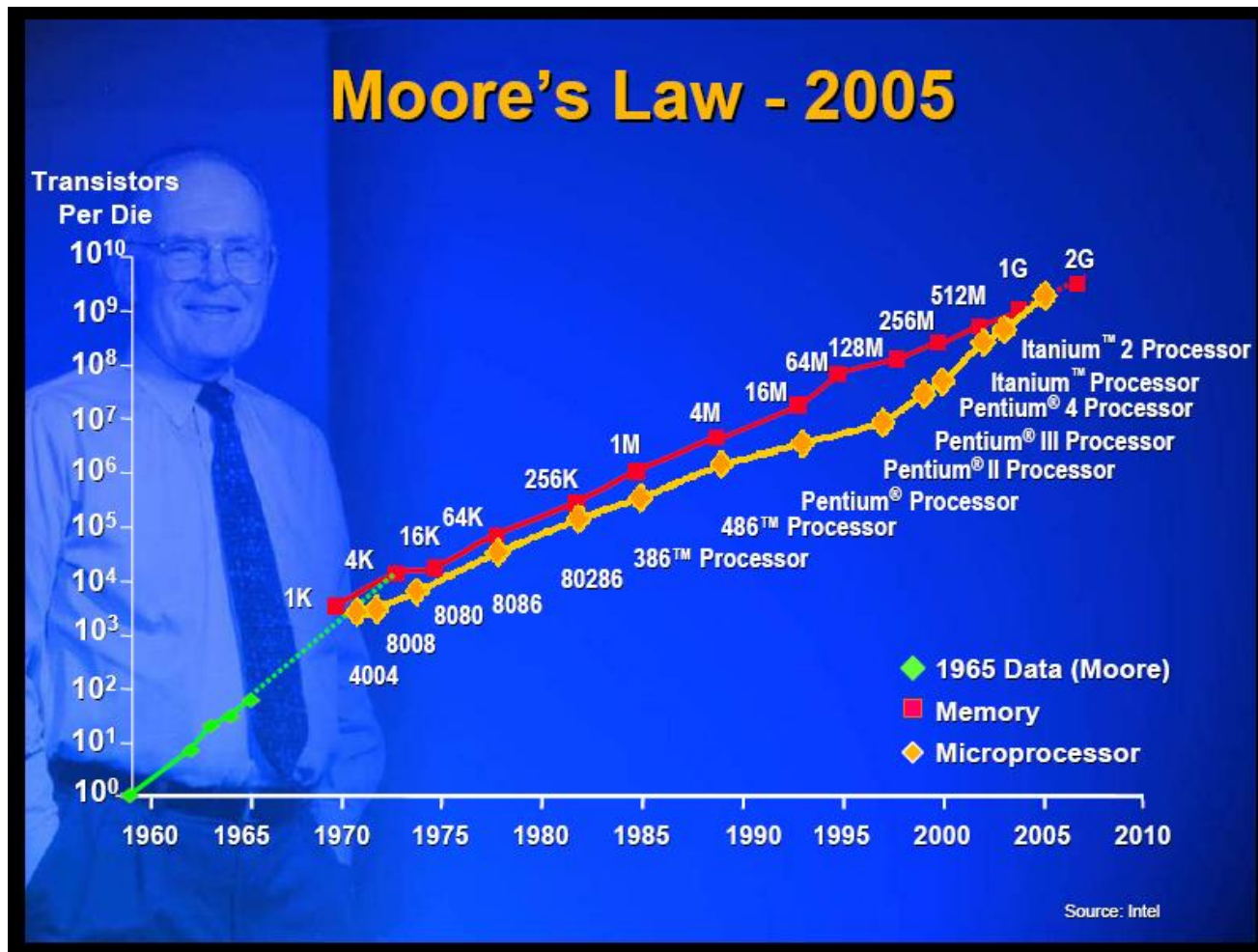


Nanoimprint Lithography

Anthony J. Lucio

Shaw Group Meeting

05/02/2013

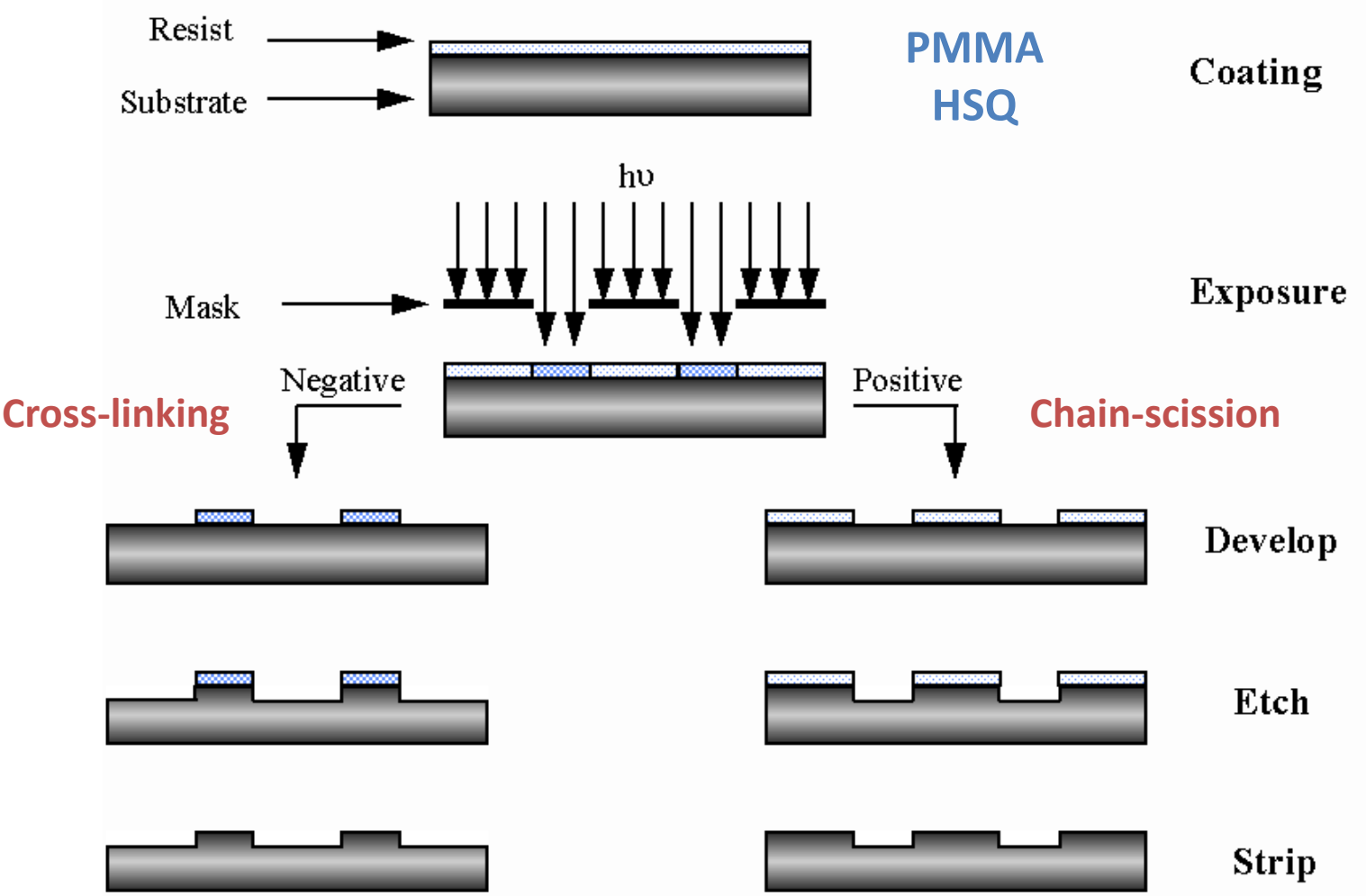


- *The number of transistors on integrated circuits doubles approximately every two years*
- When will it end?
 - **Some sources say we are at the “inflection point” for this trend!**

Requirements of Lithography

- **Critical Dimension (CD) control:**
 - Sizes must be controlled within wafer and from wafer-to-wafer during fabrication
- **Overlay:**
 - For high yield, alignment must be precisely controlled
- **Defect Control:**
 - Other than designed pattern, no additional patterns must be imaged; avoid proximity effects
- **Low Cost:**
 - Tool, resist, mask; fast step-and-repeat

Conventional Photolithography

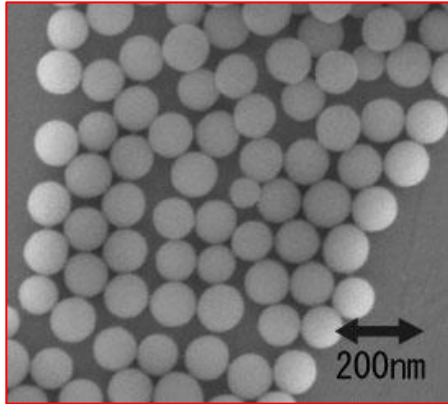


Nanoimprint Lithography (NIL)



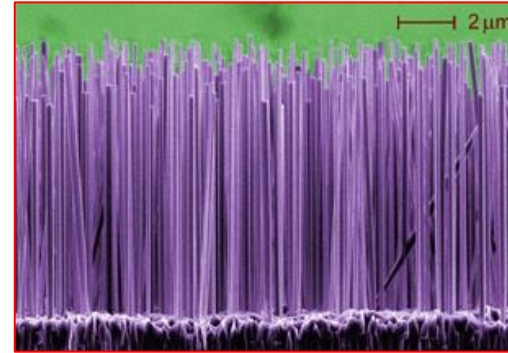
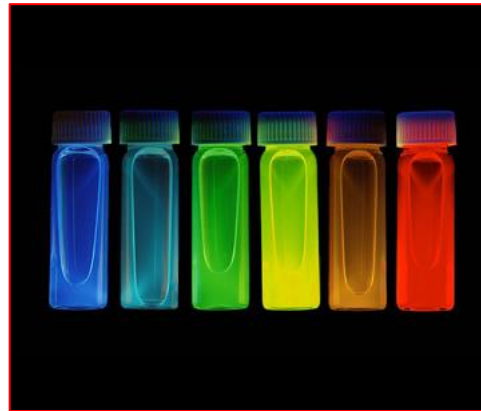
- Thermal NIL is a **three-dimensional** patterning technique with numerous application in nanotechnology
- No need for expensive/complex optics or high-energy radiation sources
- However, **relies on other lithographic techniques for template fabrication**
- Control over adhesion between mold and polymer resist is important!

Interesting Research



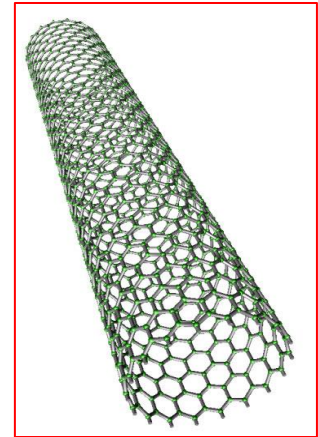
Nanoparticles

Quantum Dots



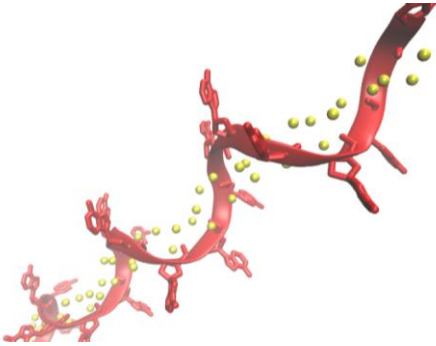
Nanowires

CNTs



- Exploiting their properties is challenging!
 - Not amenable to organization on surfaces in interconnected circuits, networks or arrays
- Self-assembled DNA nanostructures can be used as scaffolds to organize small functional nanocomponents

DNA Origami



- Large enough for conventional lithographic techniques
 - DNA is a charged molecule \Rightarrow hydrophilic surfaces
-
- The DNA origami are 2D structures obtained by folding a long genomic ss-DNA by means of hybridization with many short staples (synthetic ss-DNA); **165 × 165 nm**
 - Use “sticky ends” to attach functionalized nanostructures (CNTs, nanoparticles, etc.)

